	Hit ŝ	Search Text	DBs
24	5	photoresist or photosensitive or photocur\$4 or SU\$2)) and ((resin or resist or photoresist or	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hit	Search Text	DBs
25	23	(cylind\$5 near9 platform\$3) or roll\$4 or convey\$4) same (resin or resist or (radiation near5	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
26		<u>F</u>	DERWENT;

	Hit	Search Text	DBs
27	26	or SU\$2)) and ((resin or resist or photoresist or photocur\$4 or photosensitive) same (expos\$4 or irradiat\$4 or illuminat\$4 or cur\$4)) and (optical near16 (disks or microstructure))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
28	55	near5 sensitive) or photoresist or photosensitive or photocur\$4 or SU\$2)) and ((resin\$4 or resist	US-PGPUB; USPAT; FPRS; EPO; JPO;
29		S30 NOT S29	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hit	Search Text	DBs
30	87	near5 sensitive) or photoresist or photosensitive or photocur\$4 or SU\$2)) and ((resin\$4 or resist	US-PGPUB; USPAT; FPRS; EPO; JPO;
31	32	S32 not S30	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
32	17	<pre>((microlens\$4 or (len\$3 near6 array) or (micro near2 lens\$2)) same (web or (flexible near12 (medium or substrate) or substrate) or (plastic near5 substrate) or (polymer\$4 near9 substrate)) same (resin or resist or (radiation near5 sensitive) or photocur\$4 or SU\$2) same (optical near16 (structure or disks or microstructure or device))) and ((resin\$4 or resist or photosensitive) same (expos\$4 or irradiat\$4 or illuminat\$4 or cur\$4)) and ((web or convey\$3 or drum) same (substrate or wafer or workpiece))</pre>	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
33	264	((microlens\$4 or (len\$3 near6 array) or (micro near2 lens\$2)) same (web or (flexible near12 (medium or substrate) or substrate) or (plastic near5 substrate) or (polymer\$4 near9 substrate)) same (resin or resist or (radiation near5 sensitive) or photoresist or photosensitive or photocur\$4 or SU\$2) same (optical near16 (structure or disks or microstructure or device))) and ((resin\$4 or resist or photocur\$4 or photosensitive) same (expos\$4 or irradiat\$4 or illuminat\$4 or cur\$4))	USPAT; FPRS; EPO; JPO;